

ABSTRACT OF THE DISCLOSURE

TITLE OF THE INVENTION

FIELD EMISSION-TYPE ELECTRON SOURCE AND MANUFACTURING

A field emission-type electron source 10 is provided with a conductive substrate 1, a semiconductor layer formed on a surface of the conductive substrate 1, at least a part of the semiconductor layer being made porous, and a conductive thin film 7 formed on the semiconductor layer. Electrons injected into the conductive substrate 1 are emitted from the conductive thin film 7 through the semiconductor layer by applying a voltage between the conductive thin film 7 and the conductive substrate 1 in such a manner that the conductive thin film 7 acts as a positive electrode against the conductive substrate 1. The semiconductor layer includes a porous semiconductor layer 6 in which columnar structures 21 and porous structures 25 composed of fine semiconductor crystals of nanometer scale coexist, a surface of each of the structures being covered with an insulating film 22,24. Further, an average dimension of each of the porous structures 25 in a thickness direction of the semiconductor layer is smaller than or equal to 2 μm .

Fig. 1